

AMENDMENTS TO CLAIMS

Claim 1 (canceled)

Claim 2 (canceled)

Claim 3 (canceled)

Claim 4 (currently amended): An aligner according to claim 3 12, wherein the photomask is positioned vertically above the to-be-exposed substrate.

Claim 5 (currently amended): An aligner according to claim 3 12, wherein the photomask and the to-be-exposed substrate are positioned with a spacing nearly in a horizontal direction.

Claim 6 (canceled)

Claim 7 (currently amended): An aligner according to claim 6 13, wherein the photomask is positioned vertically above the to-be-exposed substrate.

Claim 8 (currently amended): An aligner according to claim 6 13, wherein the photomask and the to be exposed substrate are positioned with a spacing nearly in a horizontal direction.

Claim 9 (new): An aligner comprising:

- a base for resting a to-be-exposed substrate thereon;
- a sucking unit for sucking the to-be-exposed substrate on said base;
- a first control unit for relative positioning of a mask having a pattern and a portion of said substrate to be exposed to light through said pattern; and
- a second control unit interacting with said first control unit for instructing said sucking unit to suck said substrate on said base only at said portion.

Claim 10 (new): An aligner according to claim 9, wherein the photomask is positioned vertically above the to-be-exposed substrate.

Claim 11 (new): An aligner according to claim 9, wherein the photomask and the to-be-exposed substrate are positioned with a spacing nearly in a horizontal direction.

Claim 12 (new): An aligner comprising:

- a base for resting a to-be-exposed substrate thereon;
- a photomask having a predetermined pattern for projection onto the to-be-exposed substrate on said base and to be contacted with or proximate to the to-be-exposed substrate;
- a moving unit for moving at least one of said photomask and said base to change and set a relative positional relationship between them;
- a light source unit for radiating light for projection of the pattern of said photomask onto the to-be-exposed substrate on said base;
- an alignment unit for aligning the photomask and the to-be-exposed substrate in an arbitrary area of the to-be-exposed substrate;
- a sucking unit for sucking the to-be-exposed substrate at said arbitrary area on said base;
- a first control unit controlling said moving unit, said aligning unit, and said light source unit such that after alignment, the to-be-exposed substrate is exposed to light, and
- a second control unit, interacting with and responsive to said first control unit, for instructing said sucking unit to suck the to-be-exposed substrate at said arbitrary area.

Claim 13 (new): An aligner comprising:

- a base for resting a to-be-exposed substrate thereon;
- a photomask having a predetermined pattern for projection onto the to-be-exposed substrate on said base and to be contacted with the to-be-exposed substrate;
- a moving unit for moving at least one of said photomask and said base to change and set a relative positional relationship between them;
- a light source unit for radiating light for projection of the pattern of said photomask contacting the to-be-exposed substrate onto the to-be-exposed substrate on said base;

an alignment unit for aligning such that the photomask is to contact an arbitrary area of the to-be-exposed substrate;

a sucking unit for sucking the to-be-exposed substrate only at said arbitrary area on said base;

a first control unit controlling said moving unit, said aligning unit, and said light source unit such that after alignment, the to-be-exposed substrate is exposed to light, and

a second control unit, interacting with and responsive to said first control unit, for instructing said sucking unit to suck the to-be-exposed substrate at said arbitrary area.

Claim 14 (new): A method of exposing a portion of a substrate to a light pattern, comprising:

- a. providing a substrate to be exposed to light;
- b. providing a base for supporting said substrate;
- c. providing a photomask having a pattern;
- d. positioning said substrate relative to said photomask so as to expose only a portion of said substrate to said pattern;
- e. exposing said substrate to light through said mask only at said portion while sucking said substrate on said base only at said portion.

Claim 15 (new): The method of claim 14, whereby said photomask is positioned vertically above said substrate.

Claim 16 (new): The method of claim 14, whereby said photomask contacts said substrate.